

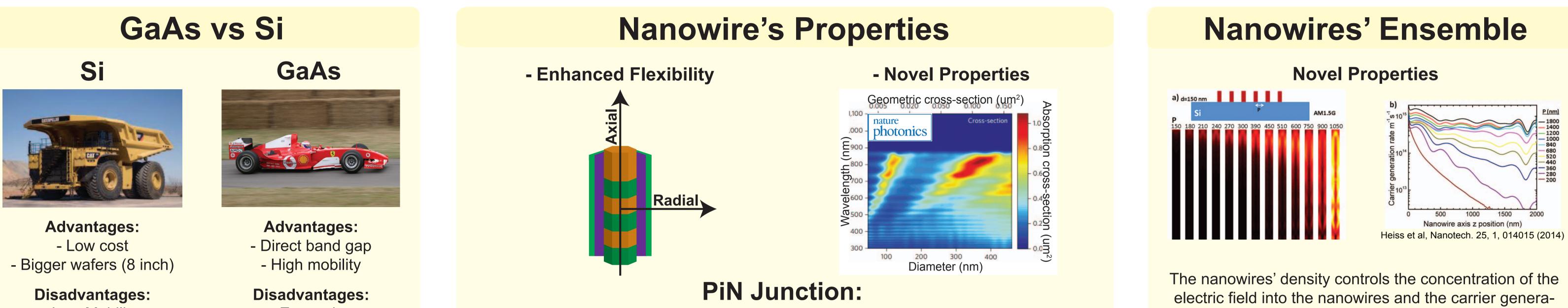
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Integration of GaAs nanowires on Si for photovoltaic applications

F. Matteini*, J. Vukajlovic*, E. Russo-Averchi, A. Dalmau Mallorqui, E. Alarcon Llado, G. Tutuncuoglu, D. Rueffer, H. Potts, A. Fontcuberta i Morral

Laboratoire des Matériaux Semiconducteurs, Ecole Politechnique Fédérale de Lausanne, 1015 Lausanne, Switzerland







-Low Mobility -Indirect band gap Fang et al J. Appl. Phys. (1990)

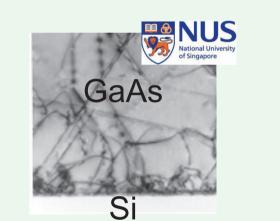
- Expensive - Poor mechanical and thermal properties

GaAs on Si



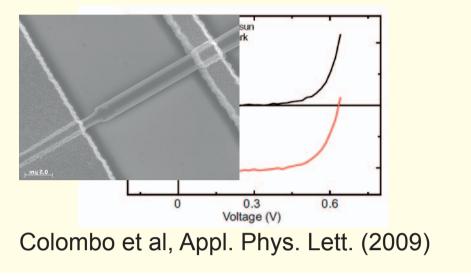
Advantages:

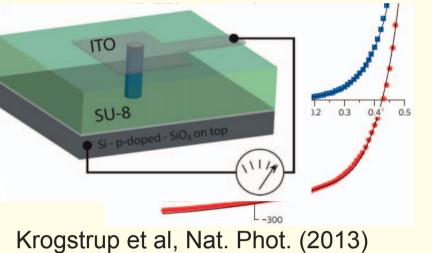
-Superior optical and electrical properties (GaAs). -Good mechanical and thermal properties (Si). -Well established technol-



Challenges:

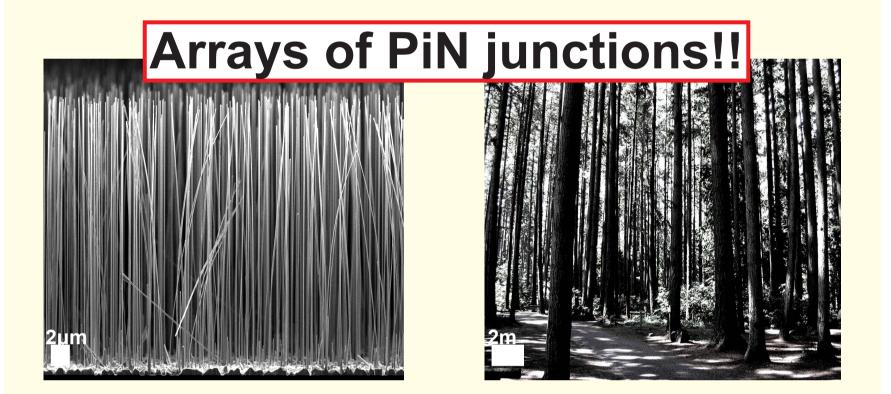
-Different thermal expansion coefficient. -Polar semiconductor with non polar. -Different lattice constants





tion rate along the nanowire axis. Achieving control over density is a key step for efficient light harvesting.

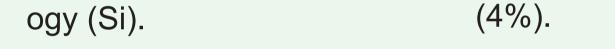
Goal:



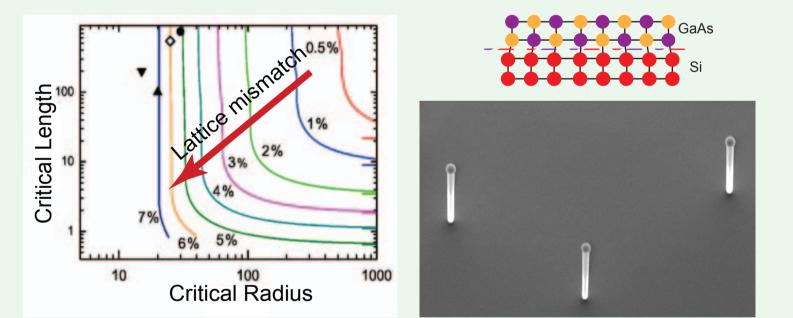
Mechanism

GaAs/Si Dual Junction

Mechanically Stacked Tandem **PDMS** E_a(GaAs)=1.42eV E_g(Si)=1.1eV



Method:



Glas and Harmand, Phys. Rev. B, (2006)

By combining GaAs and Si in a planar fashion the 4% lattice mismatch leads to cracking and defectformation. The nanowire geometry allows elastic release of the stress thanks to its radial confinement.



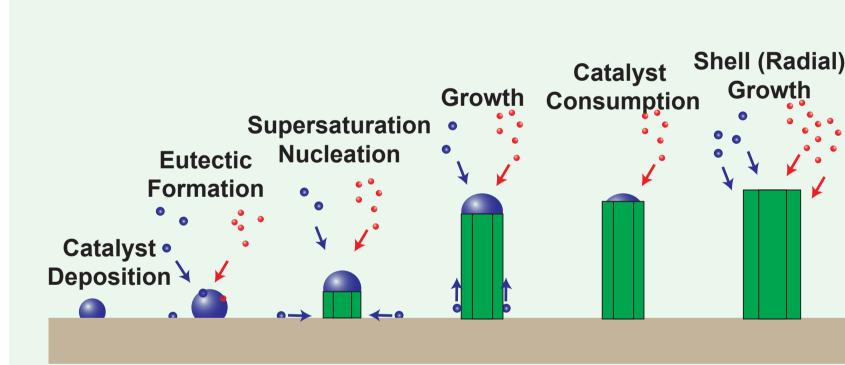
Advantages: The GaAs nanowire PiN junction is directly grown on the Si junction providing monolitic integration as grown.

Disadvantages: Since the two junctions are in series the current generated from the GaAs junction goes through the Si junction, that act as bottleneck.

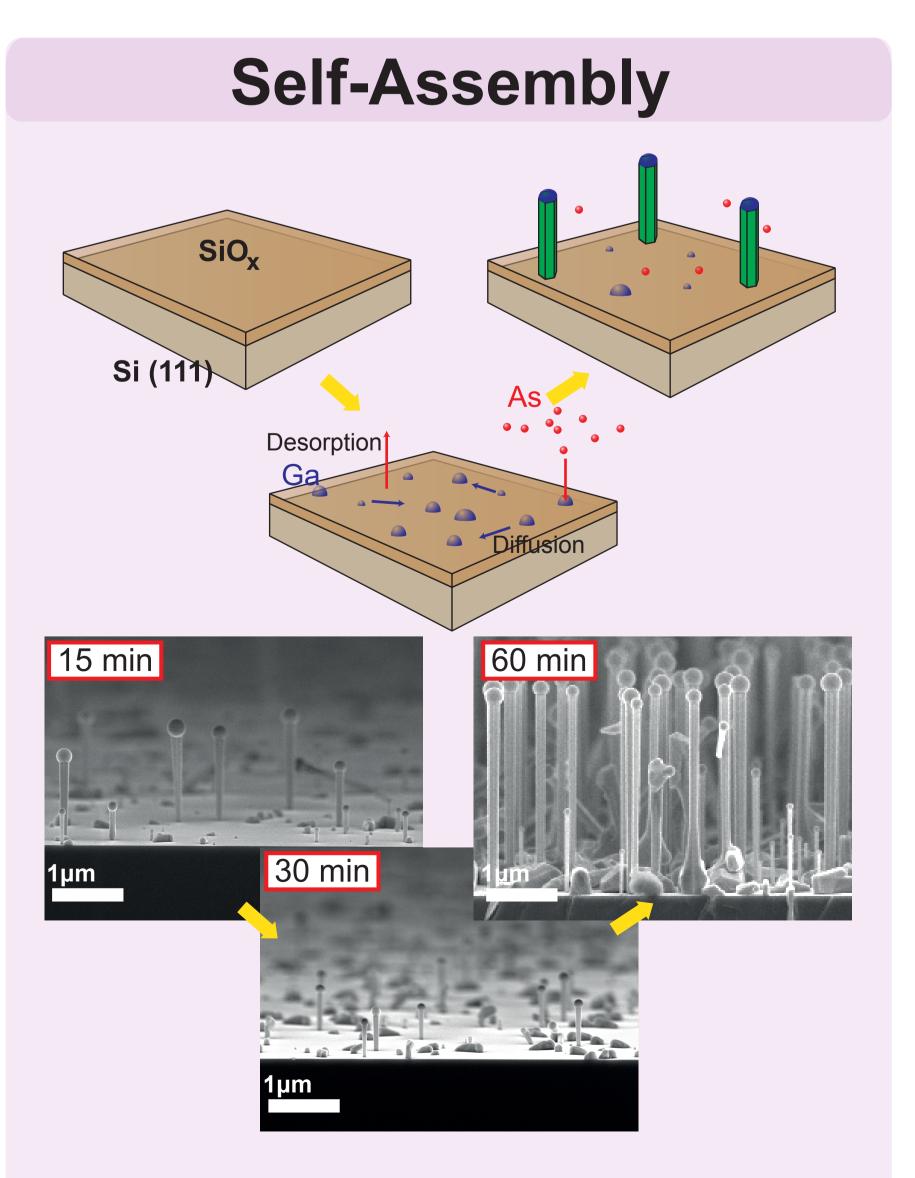
Kandala et al, phys. stat. sol. (a), 1-6 (2008)

Advantages: The GaAs junction and Si junction are in parallel, avoiding the current limitation problem.

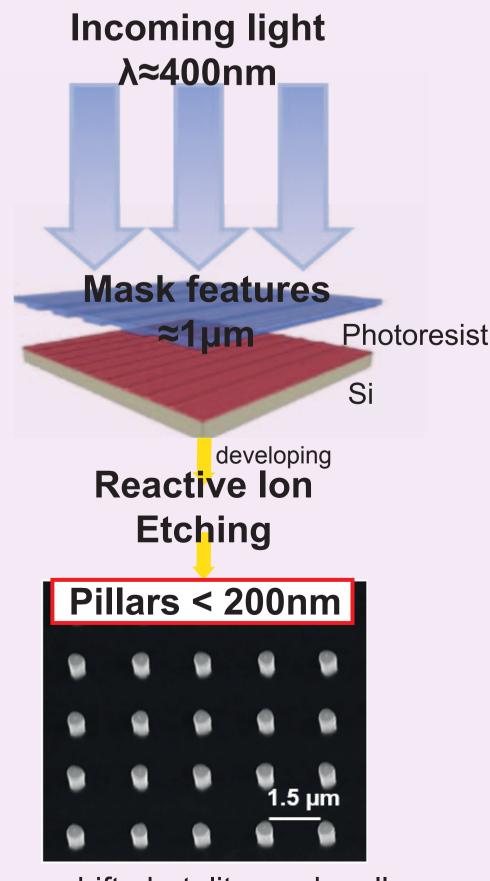
Disadvantages: The GaAs junction need additional stripping and contacting step to put them in parallel.

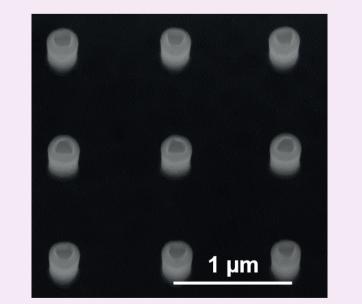


The catalyst is liquified by eutectic formation. The liquid droplet acts as reservoir until supersaturation is reached, triggering nucleation and growth.

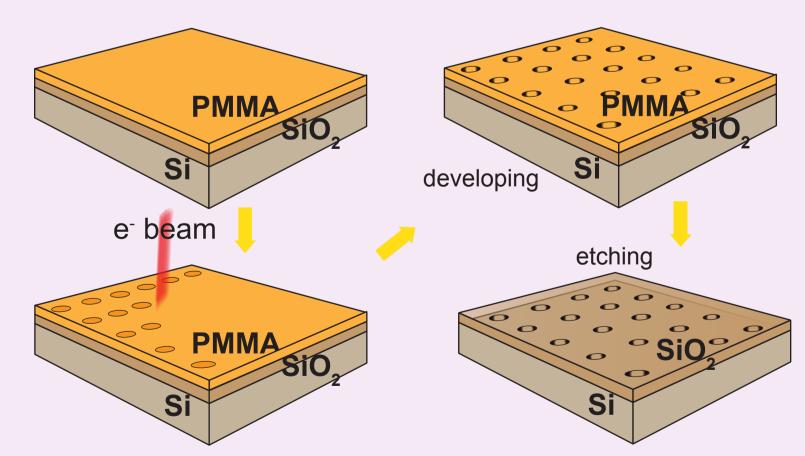


Phase-Shift Photolithography





e⁻- Beam Lithography



Vapor Liquid Solid (VLS)

In this approach the process is self-catalyzed by Ga. No catayst-predeposition is needed since Ga naturally form the liquid droplets, due to its lower vapor pressure compared to As.

Phase shift photolitography allows sub-wavelength precision.

The Si pillars are then used to make SiO₂ tubes, templates for nanowire growth.

Acknowledgments

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Patterning the substrate allows to control the nucleation position.

